# GenISys
Advancing the Standard
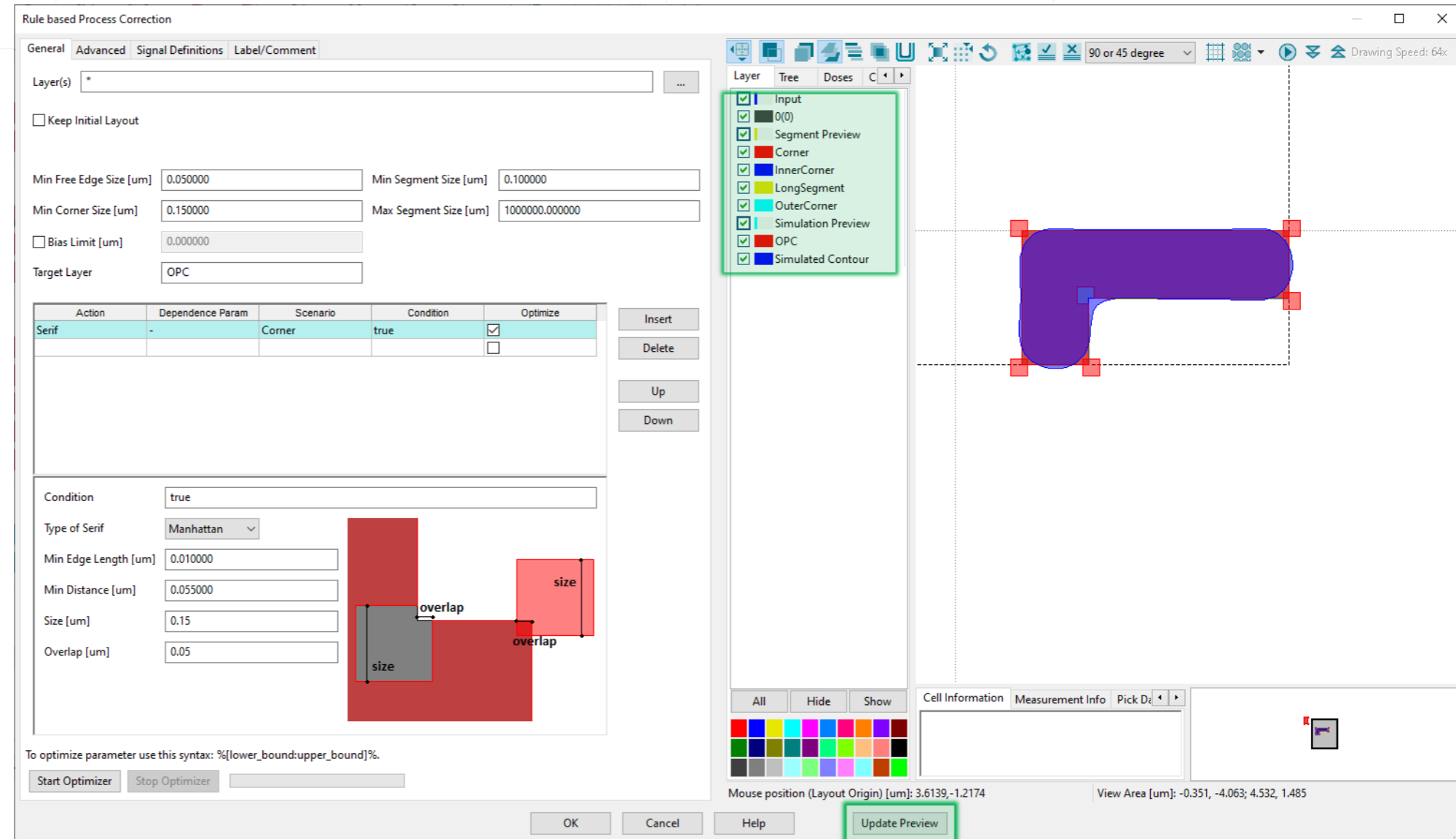
LAB
What's new v5.8

Rule OPC

Defined rules can be previewed and optimized in Rule-OPC panel.

- Rule-OPC module has to be connected to an executed exposure module or resist module. The connection to an exposure or resist module is required to get all needed parameter for the simulation.

- The preview functionallity allows the user to get a quick and easy impression of the impact by the defined rules on the used layout.

- The optimizer functionally goes one step further and optimizes defined parameters in rules, to allow an easier setup of rule sets.
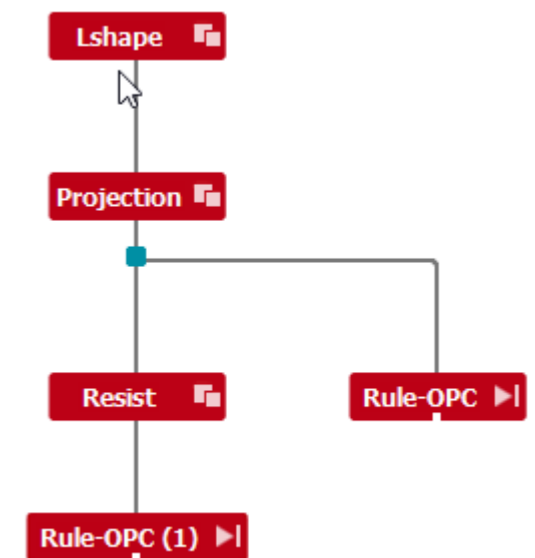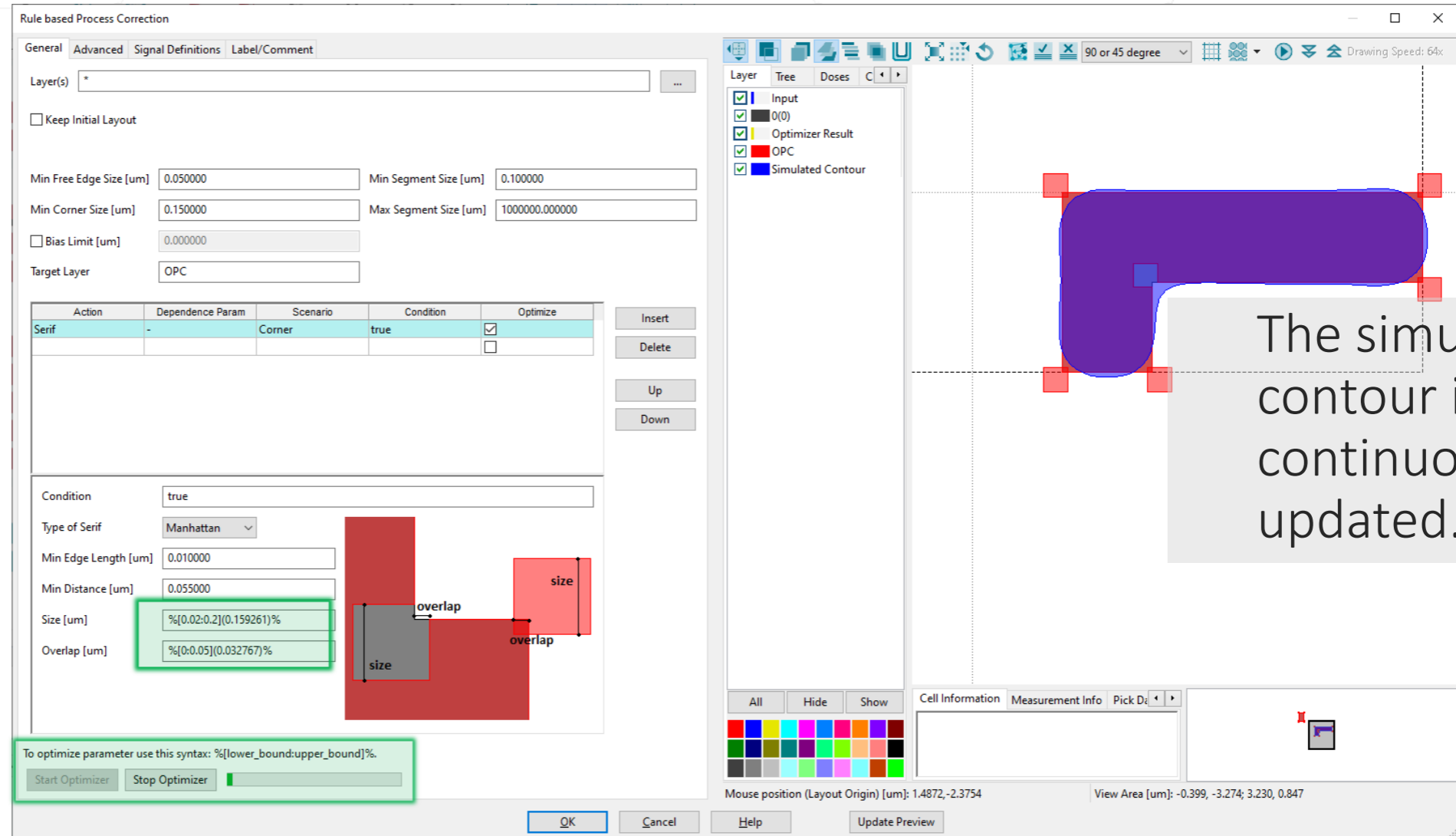
The preview functionality shows:

- Segment assignment on original layout

- Resulting layout after rule application

- Exposure simulation result of corrected layout

Define the parameter range in the rules, using the following format:

%[min value:max value]%

The simulated contour is continuously updated.

Contrast Curve Fitting
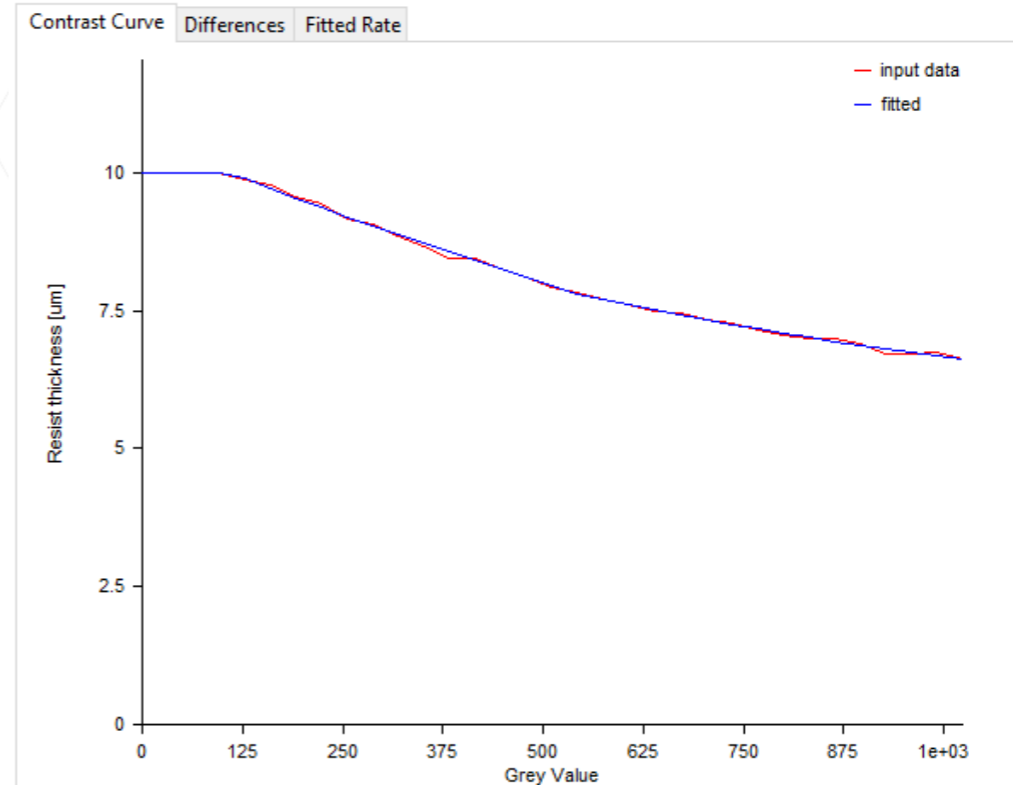
The old development rate model has been replaced with a new segmentwise developmet rate model, to ensure better fitting results for contrast curves.
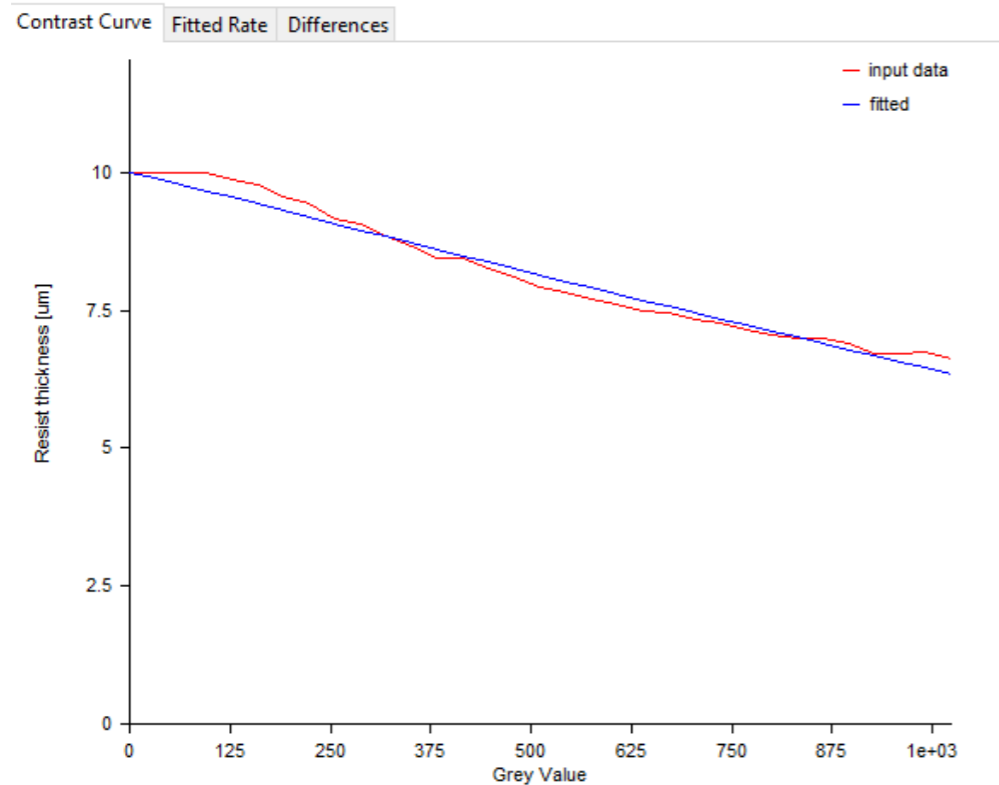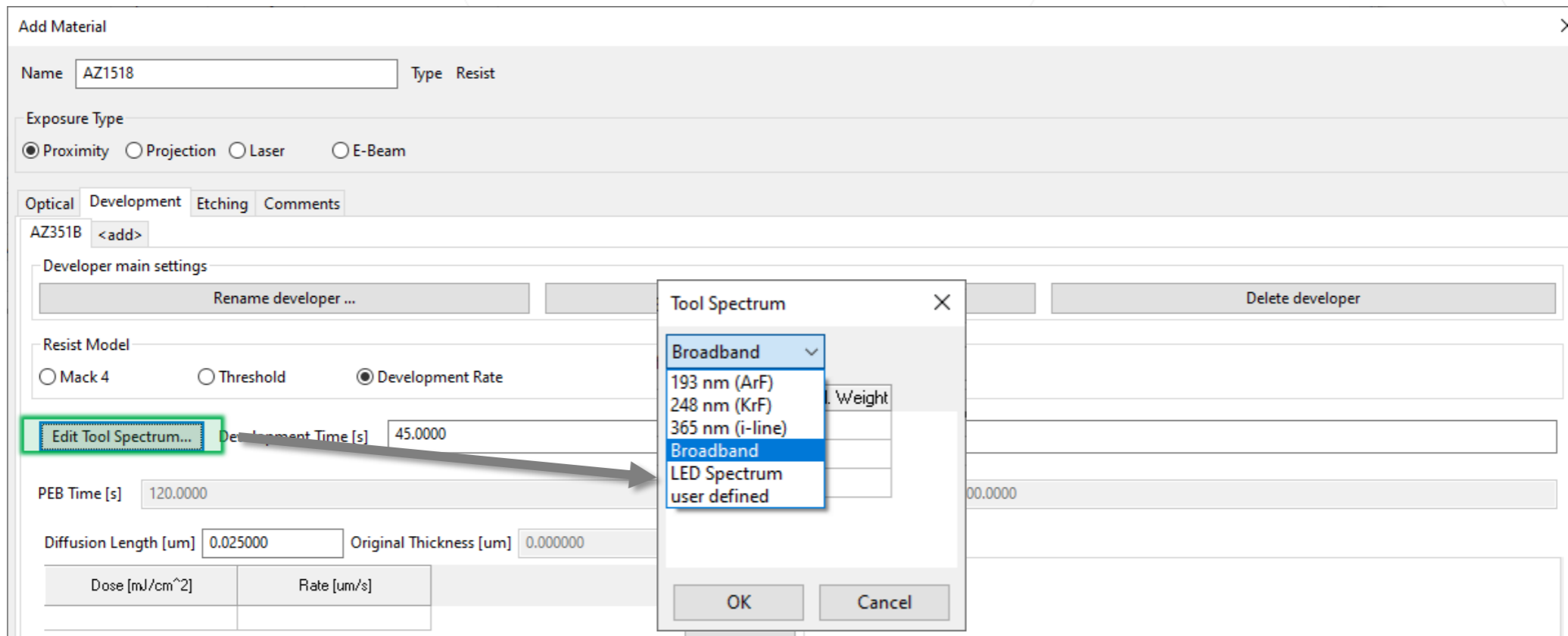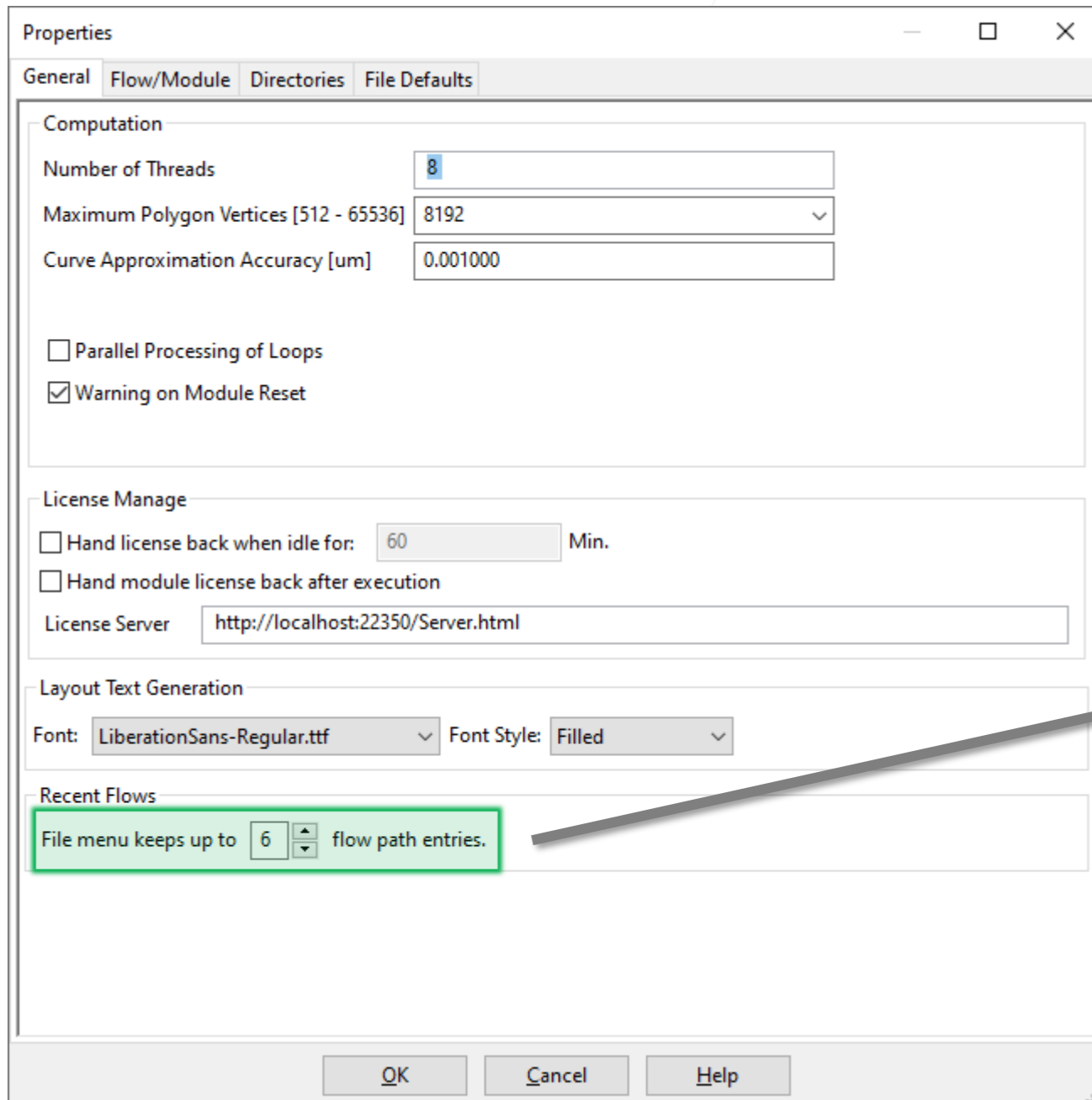
The user can now select the used exposure spectrum to ensure better fitting of the Contrast Curve.

Usability

- The number of recent flows can be adjusted via a properties setting.

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Thank You!

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